

ABSTRACT

The present invention provides a method of manufacturing a PDP that prevents defects due to dust adhering to a photomask, for example, from occurring in a structure of the PDP. In photolithography, exposure
5 is performed twice in a same process, and photomask (22) is moved within an allowable range of displacement in an exposure pattern, between a first and a second exposures. Photomask (22) is exposed twice in total before and after moving photomask (22). Region (21a), an unexposed region due to interruption of dust (22b) attached to photomask
10 (22), can be suppressed, enabling pattern exposure on photosensitive Ag paste film (21) to be favorably performed.